Title (en)

PROCESS FOR MANUFACTURING A DEPASSIVATING LAYER AND DEPASSIVATING LAYER ON AN ELECTRODE FOR AN ELECTROCHEMICAL CELL

Publication

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Application

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Priority

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Abstract (en)

[origin: US4597846A] A depassivation layer is produced on an electrode for an electrochemical cell by applying one or more layers of a metal salt solution, containing the elements to be applied, to the substrate (1) which is to be coated and is in the form of a porous plate, by means of rolling an elastic roller (2) over the substrate, with the insertion of a solution carrier (3) in the form of felt or paper, and then drying the layer and subjecting it to a chemical/thermal treatment in air (heat treatment at 450 DEG C.). Good depassivation layers with a relatively small noble metal content can be produced in this way. The depassivation layer which, in the form of a homogeneous film, is at least partially coherent contains, as a finely divided, sub-microscopic mixture, electronically conductive sub-oxides/oxides of the substrate (1) in addition to noble metals/noble metal oxides, and it can also contain further components, such as SnO2.

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C25B 11/00; C25B 11/06

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